PATENT

Docket No.: A-71606-1/MSS (463035-870)

ED STATES PATENT AND TRADEMARK OFFICE

In re application of:

HELMS et al.

Serial No: 10/519,331

Filed: December 22, 2004

Title: Method for Energy-Assisted Atomic

Layer Deposition and Removal

Examiner: To Be Assigned

Art Unit No: To Be Assigned

San Francisco, CA 94111

Date: January 24, 2005

SUBMISSION OF FORMAL DRAWINGS

Commissioner for Patents.

Attention: Official Draftsperson

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Enclosed herewith are eleven (11) sheets of formal drawings consisting of Figs. 1-3J for the above-identified patent application.

The Commissioner is authorized to charge any underpayment of fees or credit any overpayment to counsel's Deposit Account No. 50-2319 (A-71606-1/MSS (463035-870)).

Respectfully submitted,

Date: January 24, 2005

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H _f O ₂
SiO ₂ Interface
Si

FIG. 1

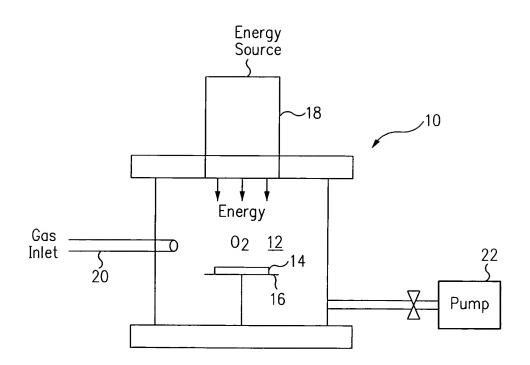


FIG. 2



Si

O Low Temp.
ALD Hf
Precursor

H Passivated Si Wafer

Surface

Radical species of Low Temp. LD Hf precursor

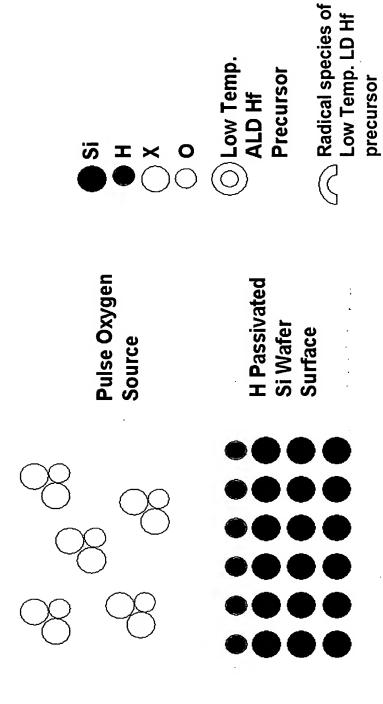
(Hf) Hafnium atom

(Hf) Hafnium atom

FIG-3B



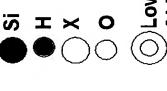
Atomic Layer Exchange For 5 EOT Gate Dielectric







Pulse Oxygen Source



O Low Temp.
ALD Hf
Precursor

H Passivated

Si Wafer Surface



FIG-3C

(Hf) Hafnium atom



Activate the

Oxygen Source

H Passivated Si Wafer Surface

O Low Temp. ALD Hf Precursor

Radical species of Low Temp. LD Hf precursor

(Hf) Hafnium atom

FIG-3D



Purge

O Low Temp.
ALD Hf
Precursor

Radical species of Low Temp. LD Hf precursor

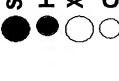
Hf Hafnium atom

FIG-3E





Pulse Low Temperature ALD Hf Precursor



O Low Temp. ALD Hf Precursor



(Hf) Hafnium atom precursor



Activate Low Temp ALD Hf Precursor

O Low Temp.
ALD Hf
Precursor

Radical species of Low Temp. LD Hf

precursor

(Hf) Hafnium atom

FIG-3G



ALD Reaction

and Ar Purge

O Low Temp.
ALD Hf
Precursor

Radical species of Low Temp. LD Hf precursor

(Hf) Hafnium atom

FIG-3H



Pulse Oxygen Source and Activate

0

O Low Temp. ALD Hf Precursor

Radical species of Low Temp. LD Hf precursor

(Hf) Hafnium atom



and Continue with Hf Source Purge

Pulse

O Low Temp. ALD Hf Precursor

Radical species of Low Temp. LD Hf precursor

(Hf) Hafnium atom

FIG-3J